



Welcome to  
046188 Winter semester 2012  
Mixed Signal Electronic Circuits  
Instructor: Dr. M. Moyal

## Lecture 5a

***Cont. Mismatches in Mixed Signal Circuits***

Mismatches in CMOS devices.

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# Summary lect. 2-4



## Eq. and definitions

$$SNR = \frac{\text{Signal Power}}{\text{Total Noise Power}}$$

$$SNDR = \frac{\text{Signal Power}}{\text{Noise and Distortion Power}}$$

$$ENOB = \frac{SNDR(dB) - 1.76dB}{6.02dB}$$

$$SFDR = \frac{\text{Signal Power}}{\text{Largest Spurious Power}}$$

$$THD = \frac{\text{Total Distortion Power}}{\text{Signal Power}}$$

$$V_{noise}^2 = 4 \cdot k \cdot T \cdot R \cdot \Delta f$$

$$1K\Omega \Rightarrow 4.09 \cdot (\eta V / \sqrt{Hz})$$

Noise in a resistor

$$V_{in\_noise}^2 = \frac{(2/3) \cdot 4 \cdot k \cdot T \cdot \gamma \cdot \Delta f}{g_m}$$

$$V_{in\_noise}^2 = \frac{K_o \cdot k \cdot T}{W \cdot L \cdot f} \cdot \Delta f$$

Noise in a transistor  
(CMOS)

$$R = \frac{L}{W} R_{\square} = \frac{L}{W} \cdot \frac{\rho}{x_j}$$

$$C = \frac{\epsilon_0 \epsilon_r}{t_{ox}} WL$$

$$C = C_a \times \text{Area} = C_a \times W \times L$$

# MISMATCHES



**One of the most critical parameters in Mixed signal design.**

**Mostly ignored with normal simulators**

# Mismatches- modelling- "Pelgrom rule"



## MISMATCHING In Current-Steering D/A Converters

IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 24, NO. 5, OCTOBER 1989

### Matching Properties of MOS Transistors



MARCEL J. M. PELGROM, MEMBER, IEEE, AAD C. J. DUINMAIJER,  
AND ANTON P. G. WELBERS

'Random' mismatch

'Systematic' mismatch

Transistor sizing

Layout techniques

$$\sigma_{V_T} = \frac{A_{V_T}}{\sqrt{WL}} + S_{V_T}^2 D^2$$

$$\frac{\sigma_{\beta}}{\beta} = \frac{A_{\beta}}{\sqrt{WL}} + S_{\beta}^2 D^2$$

$$\frac{\sigma_{\gamma}}{\gamma} = \frac{A_{\gamma}}{\sqrt{WL}} + S_{\gamma}^2 D^2$$



First test:

Is it a current source mode ?

Is it a voltage mode device ?

Is it a switch ?

Mixed signal design must address:

Can we ignore/neglect the error ?

If not can we “calibrate” or fix the errors ?

## Mismatches- $V_{th}$ .



Process deviation: threshold voltage is highly process dependent:

$$V_{th} = V_{FB} - Q_{ss}/C_{ox} + V_{sub} + 2|\Phi_p| + |Q_d|/C_{ox}$$

where:

$V_{FB}$ - flat band voltage,

$Q_{ss}$  – surface charge per unit area,

$V_{sub}$  – substrate voltage,

$2|\Phi_p|$  - voltage required for strong inversion, doping gradients

$Q_d$  – depletion charge per unit area in the depletion region

$C_{ox}$  – oxide capacitance per  $\mu m^2$ , depends on oxide thickness

All of them except  $V_{sub}$  are process dependent and randomly or graded distributed

Layout mismatch: Voltage drop on along power line can cause graded error

# Mismatches- History

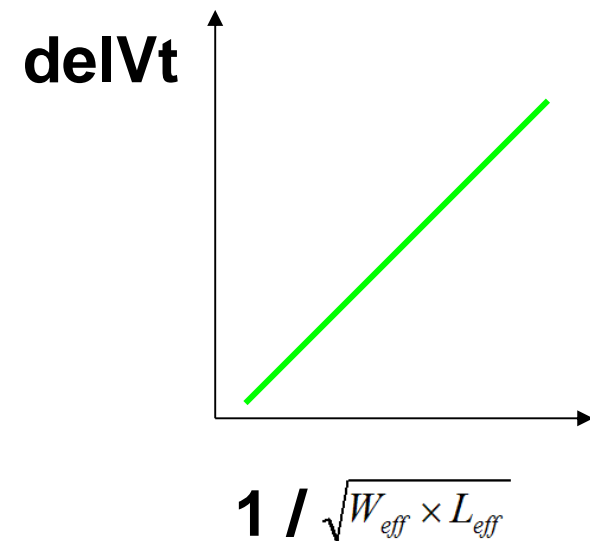
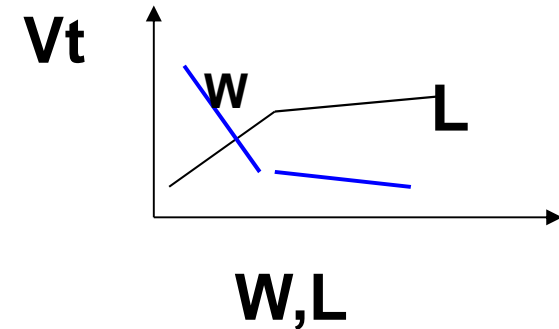


First belief was based on measured data :  
Very L dependent and Very W dependent

Low L  $V_t$  goes down – so variations is large  
Low W  $V_t$  goes up – so variation is large

Today Pelgrom law define most mismatches  
as function of area  $W \times L$

$$\sigma(\Delta V_T) = \frac{C_1}{\sqrt{W_{eff} \times L_{eff}}}$$



## Note on C1



C1 is in today design ~ 2-10 mV for  $W \times L = 1$  ( $\mu \times \mu$ )

C1 has strong dependency on manufacturing – we do not have much control

C1 follow ~ 1.5  $t_{ox}$  (in nm  $\rightarrow$  mv) as a “rule of thumb” – use thin oxide devices

C1 can be different for different layouts – we have control

### Example for C1.

**~ 3nm  $T_{ox}$  --\_ 90nm process ~ 4.5mv x  $\mu\text{m}$**

**0.18 $\mu\text{m}$  process  $t_{ox}=4\text{nm}$  ~ 6mv x  $\mu\text{m}$**

**3.3v process,  $t_{ox}\sim 7\text{nm}$  ~ 10mv x  $\mu\text{m}$**



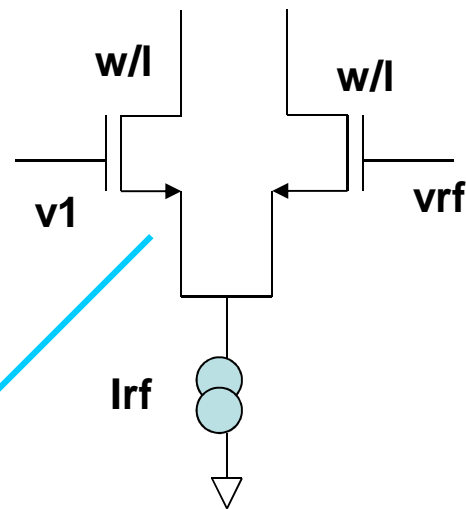
# V Mismatches- Saturation



$$\sigma^2(I_D) = \frac{\beta^2}{2} (V_{GS} - V_T)^2 * \sigma^2(\Delta V_T) + I_D^2 * \sigma^2\left(\frac{\Delta L}{L}\right)$$

$$\beta = \mu \cdot C_{ox} \cdot \frac{W}{L}$$

“never mind” this.. Create a design model



amplifiers, comparators offset.

$$\sigma(\Delta V_T) = \frac{C_1}{\sqrt{W_{eff} \times L_{eff}}}$$



$$\propto \frac{1}{\sqrt{W_{eff} \times L_{eff}}}$$

increase area for better results  
What happen to input cap ?

# I Mismatches- Saturation: method I



1

$$I = k \frac{W}{2L} (V_{GS} - V_T)^2 = \alpha (V_{GS} - V_T)^2$$

$$\Delta I + I = k \frac{W}{2L} (V_{GS} + \Delta V - V_T)^2 = \alpha (V_{GS} + \Delta V - V_T)^2 \quad V_{GS} = V_B$$

$$\Delta I = \alpha \left[ (V_{GS} + \Delta V - V_T)^2 - (V_{GS} - V_T)^2 \right]$$

$$= \alpha \left[ (V_{GS} - V_T)^2 + \Delta V^2 + 2(V_{GS} - V_T)\Delta V - (V_{GS} - V_T)^2 \right]$$

$$\Delta I \approx \alpha \cdot 2(V_{GS} - V_T)\Delta V$$

$$\frac{\Delta I}{I} = \frac{\alpha \cdot 2(V_{GS} - V_T)\Delta V}{\alpha (V_{GS} - V_T)^2} = \frac{2}{V_{GS} - V_T} \cdot \Delta V = \left[ \frac{2}{V_{GS} - V_T} \right] \frac{C_1}{\sqrt{W \times L}}$$

$$\left( \frac{\Delta I}{I} \right)^2 = \left[ \frac{C_1}{\sqrt{W \times L}} \right]^2 \frac{4}{(V_{GS} - V_T)^2}$$

one way.

$$\frac{\sigma^2(I_D)}{I_D^2} = \left\{ \frac{\beta}{I_D} \sigma^2(\Delta V_T) + \sigma^2\left(\frac{\Delta L}{L}\right) \right\} = \left\{ \frac{2}{(V_{GS} - V_T)^2} \sigma^2(\Delta V_T) + \sigma^2\left(\frac{\Delta L}{L}\right) \right\}$$

# I Mismatches- Saturation- second method



$$\frac{\Delta I}{I} = \frac{g_m \cdot \Delta V}{I} = \frac{\sqrt{2k \frac{W}{L} \cdot I}}{I} \Delta V$$

$$= \frac{(2k \frac{W}{L})}{\sqrt{I}} \cdot \Delta V = \frac{\sqrt{2k \frac{W}{L}}}{\sqrt{k \frac{W}{2L} (V_{GS} - V_T)}} \cdot \Delta V = \frac{2}{V_{GS} - V_T} \Delta V$$

$$\Delta I = g_m \cdot \Delta V$$

$$\frac{\Delta I}{I} = \frac{2}{V_{GS} - V_T} \cdot \frac{C_1}{\sqrt{W \times L}}$$

Second way.

LARGE  $V_{GS}$

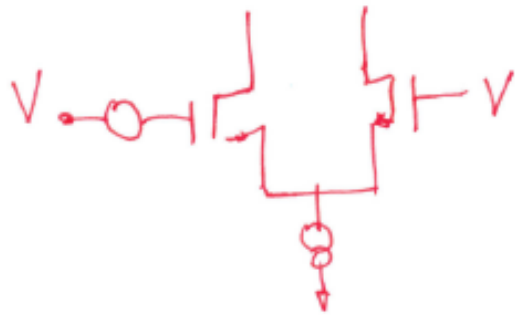
**In spice- monte-carlo can  
Add also w and L mismatches**

$$\frac{\Delta I_D}{I_D} = \left[ \left( \frac{\Delta \frac{W}{L}}{\frac{W}{L}} \right) + \left( \frac{2 \Delta V_T}{V_{GS} - V_T} \right) \right]$$

# Mismatches/offset Vs. L, W,



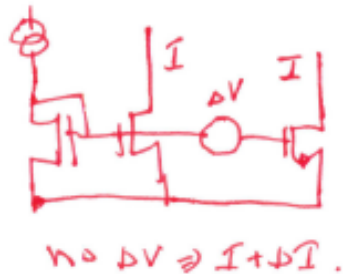
Amplifiers comparators MINIMIZE offset  
(Mismatches)



$$\Delta V = \frac{C}{\sqrt{W \times L}} \Rightarrow \text{INCREASE } W \times L \text{ AREA}$$

$$\approx \frac{1}{\sqrt{W \times L}}$$

CURRENT SOURCES MINIMIZE I offset, MISMATCH.

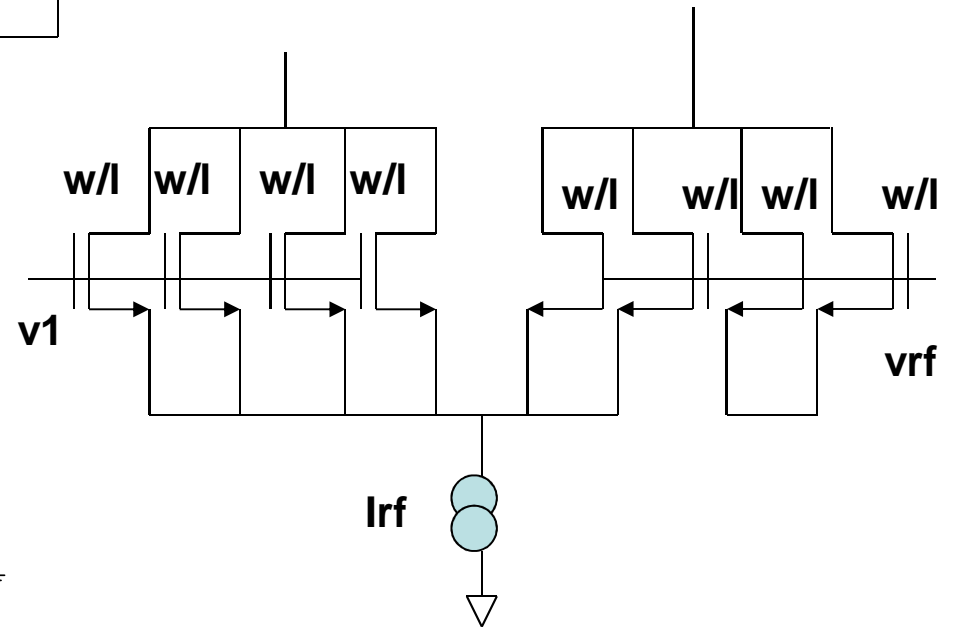
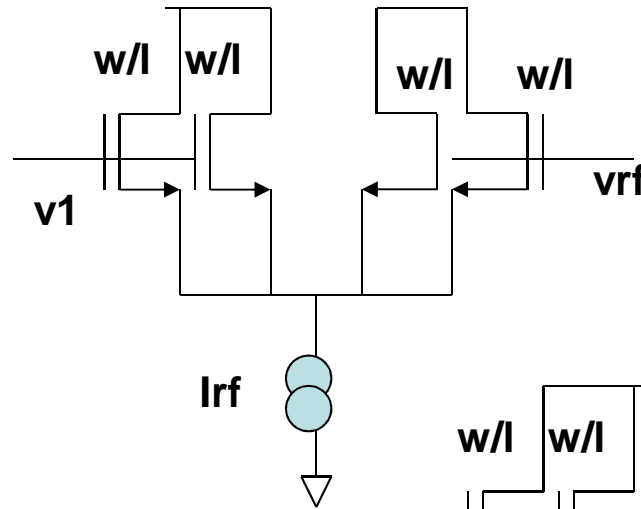
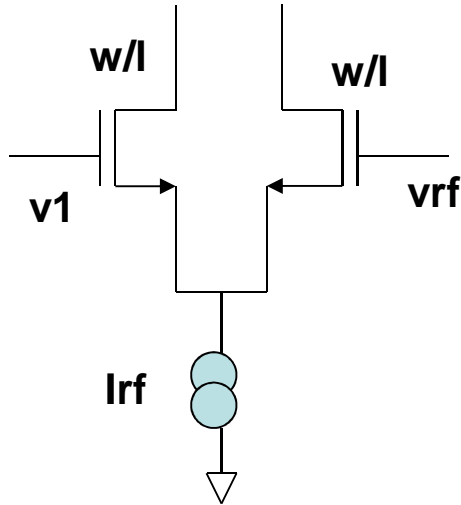


No  $\Delta V \Rightarrow I + \Delta I$ .

$$\Delta I = g_m \cdot \Delta V = \frac{g_m C_1}{\sqrt{W \times L}} = \frac{\sqrt{(k \frac{W}{L} 2I)} C_1}{\sqrt{W \times L}}$$

$$\Delta I = \frac{C \sqrt{2I M_0 \omega_x}}{L} \sim \frac{1}{L} \quad \boxed{\text{LARGER } L}$$

# Example: Mismatches/offset



$$\sigma(\Delta V_T) = \frac{C_1}{\sqrt{W_{eff} \times L_{eff}}}$$

$$\sigma(\Delta V_T) = \frac{C_1}{\sqrt{2W_{eff} \times L_{eff}}}$$

$$\sigma(\Delta V_T) = \frac{C_1}{2\sqrt{W_{eff} \times L_{eff}}}$$

**4x transistor area = 1/2 offset improvement**

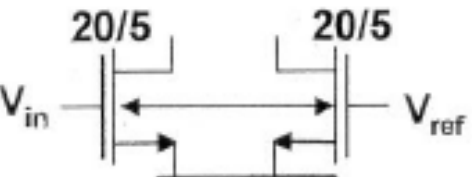


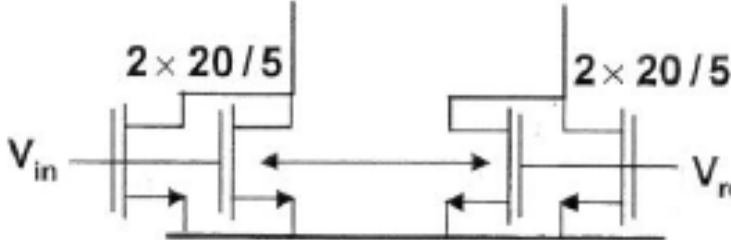
### Calculate the Matching

$$\sigma_{VT} = \frac{A_{VT}}{\sqrt{WL}} \quad A_{VT} = 10 \text{ mV}\mu\text{m}$$

$V_{ref}$  is fixed;

Calculate the input-voltage-referred standard deviation


$$\sigma_{\Delta(V_{in}-V_{ref})} = \frac{10}{\sqrt{100}} [mV]$$


$$\sigma_{\Delta(V_{in}-V_{ref})} = \frac{10}{\sqrt{200}} [mV]$$



**END lecture 5a**

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